



Institut de Ciències Fotòniques Ultrafast electro-absorption graphene modulators with a 2D-3D integration of hBN and a high-k dielectric

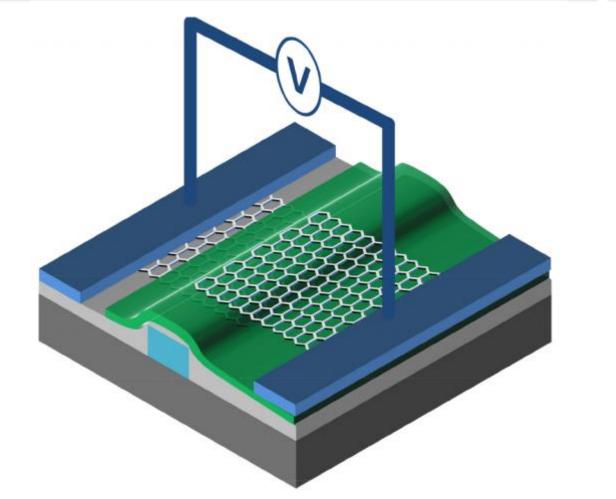
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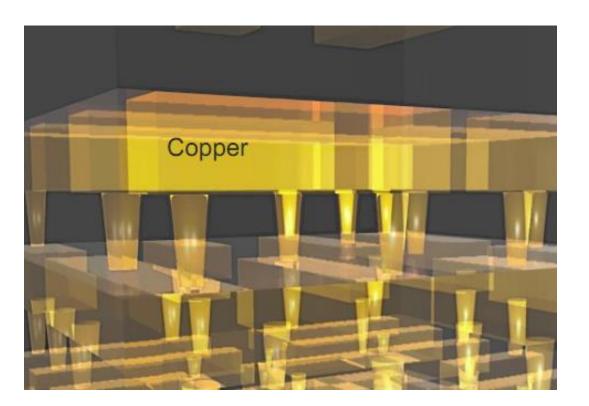
INTRODUCTION

DEVICE CONCEPT & BASIC PRINCIPLE

- Electro-absorption^[1] (EA) and/or phase modulators
 ^[2] are the basic building blocks (transmitters) for optical interconnects.
- Double-layer (DL) graphene modulators, altough a promising configuration for graphene-based modulators, suffer from a fundamental trade-off between speed and modulation efficiency^[3].
- In order to enhance both the speed (f_{3dB} bandwidth) and the modulation efficiency (β), i.e. minimize the power consumption, we integrate a high-κ dielectric material, like Hafnia (HfO₂), in between hBN flakes.
- The proposed hBN-HfO₂-hBN dielectric yields a high modulation efficiency (β=2.2dB/V) as well as a high modulation speed (BW>40GHz). Moreover, the addition of HfO₂ increases the robustness of the hBN dielectric ^[4], paving the way for the use of DL graphene modulators in on-chip interconnect applications.



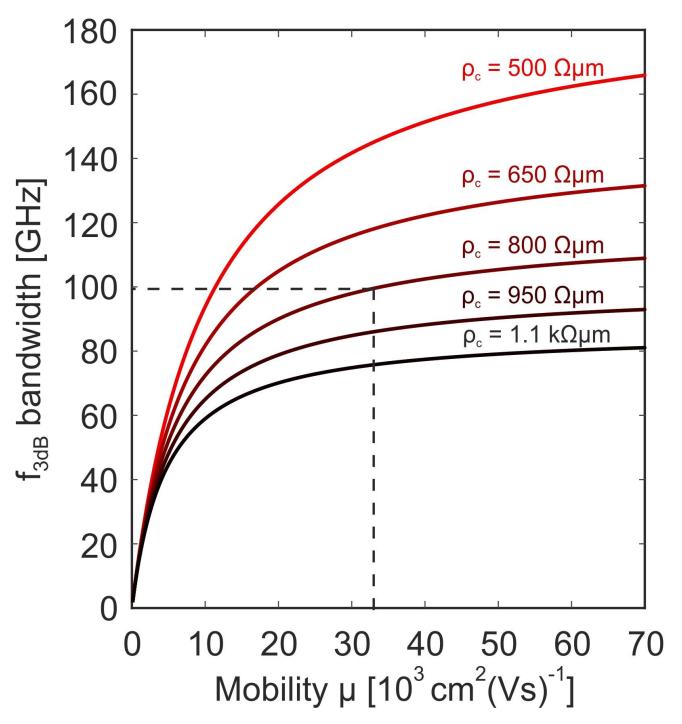
M. Mohsin et al., Optics Express Vol. 22, Issue 12. pp. 15292-15297 (2014).



Out-of-plane copper-based electrical interconnect (picture source: www.extremetech.com).

2D-3D integration of a high-к dielectric in between hBN

 The 2D-3D integration of hBN and a high-κ dielectric preserves the intrinsic high mobility (μ) of graphene and enhances the robustness of the insulating layer. Effects of an $hBN-HfO_2-hBN$ dielectric on the f_{3dB} bandwidth



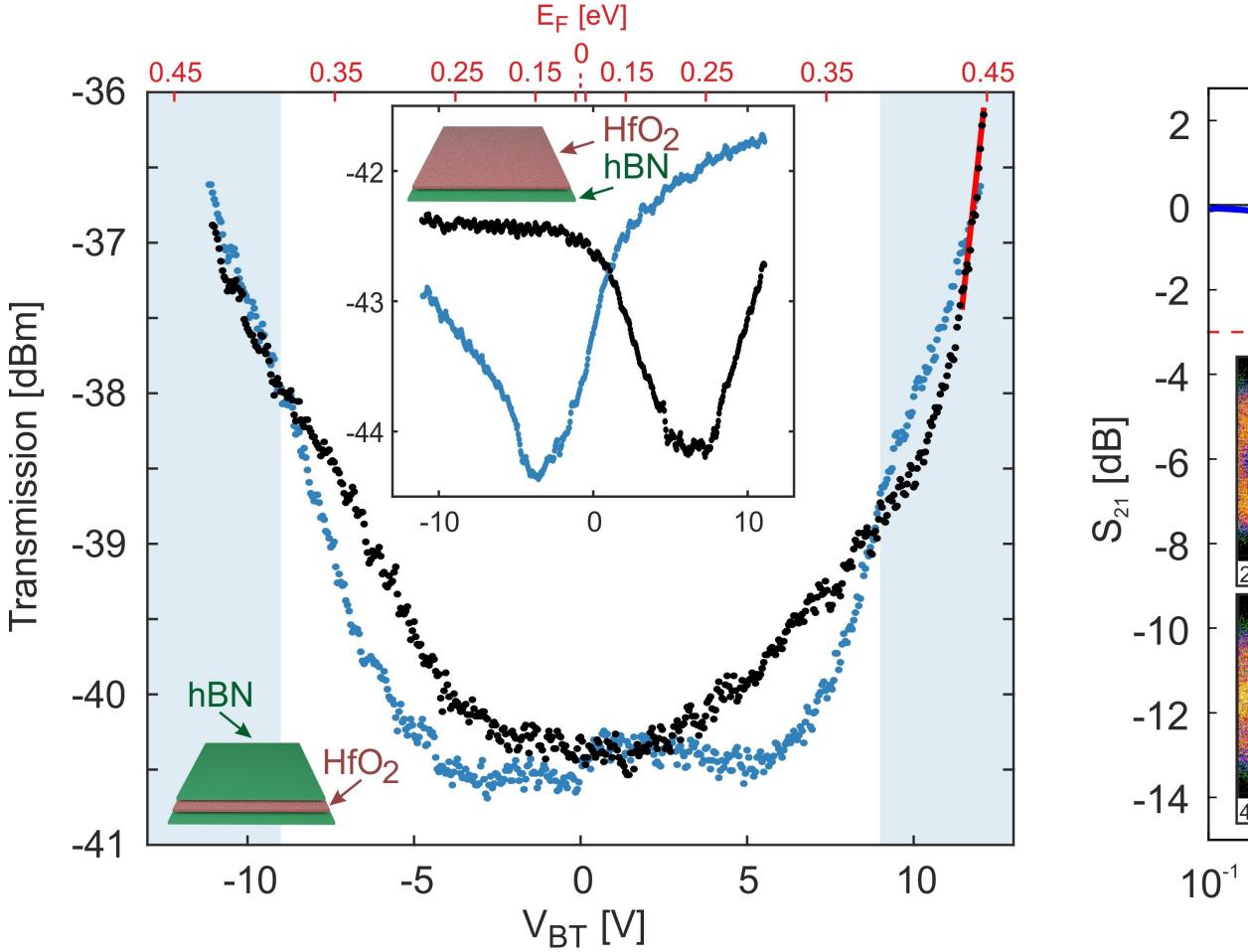
• The graphene mobility (μ) together with the contact resistivity (ρ_c) are crucial to achieve a high f_{3dB} bandwidth in a DL graphene modulator.

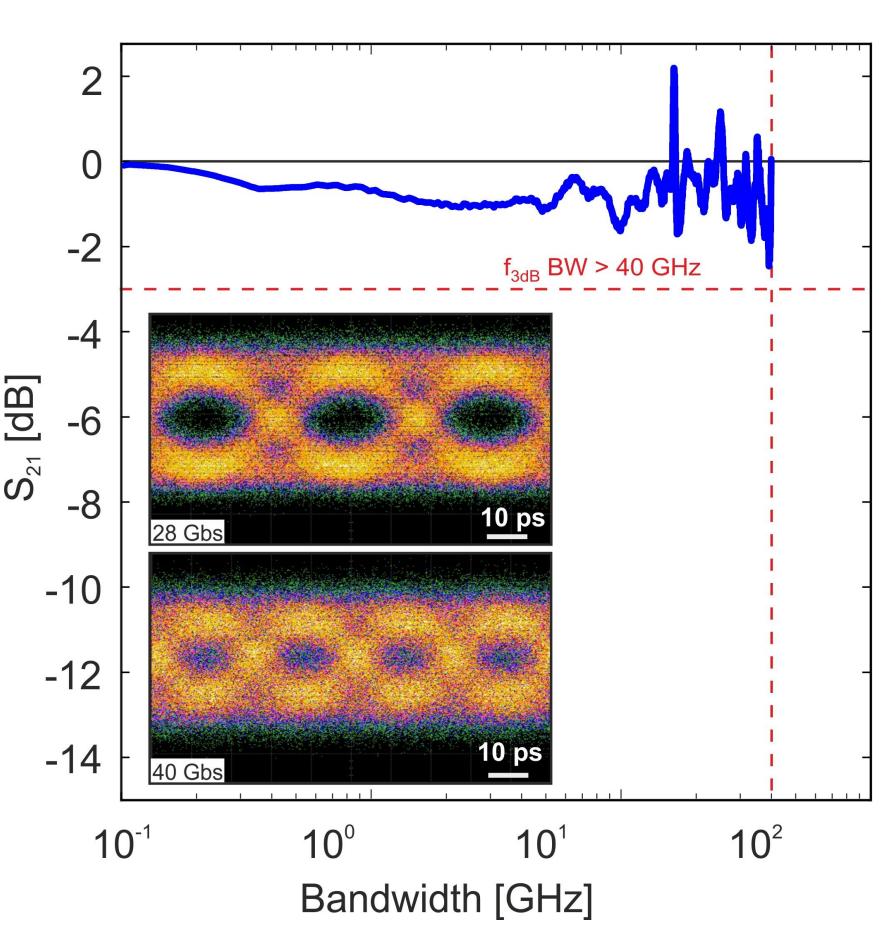
DEVICE CHARACTERIZATION

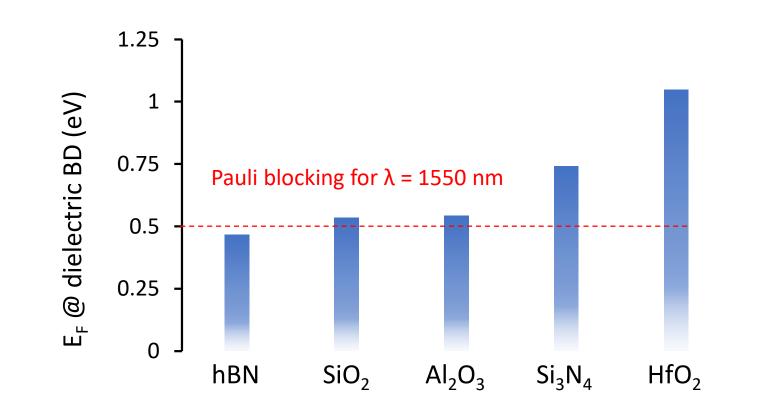
Transmission curves:

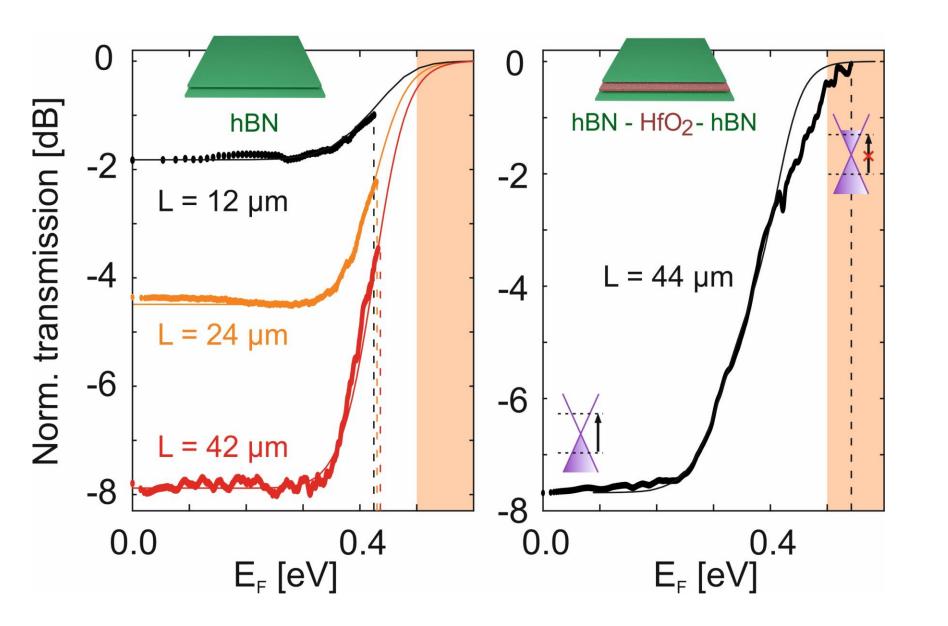
Speed measurements:

Robust dielectric material:

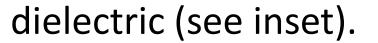








- We obtain a modulation efficiency $\beta = 2.2 dB/V$ (red fit).
- We obtain a reduced hysteresis compared to hBN-HfO₂
- The f_{3dB} bandwidth (BW>40GHz) is setup limited.
 We measure an open eye-diagram at modulation
- The hBN-HfO₂-hBN dielectric allows a higher E_F (vertical



speeds as high as 40Gbps (inset).

dashed lines) enabling Pauli blocking operation.

CONCLUSIONS & OUTLOOK

- We have experimentally demonstrated the integration of a high-κ dielectric with hBN in a electro-absorption DL graphene modulator.
- The EA modulators with a hBN-HfO₂-hBN dielectric combination conserve the outstanding properties of hBN-encapsulated devices (high electronic mobility) while improving the robustness of the dielectric.
- The 2D-3D integration of HfO₂ and hBN paves the way for interconnects applications and more specifically for phase modulators working in the Pauli blocking regime.

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[2] V. Sorianello et.al. "Graphene-Silicon phase modulators with gigahertz bandwidth", Nature Photonics **12**, 40–44 (2018).

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[4] Y. Hattori *et al. "Anisotropic Dielectric Breakdown Strength of Single Crystal Hexagonal Boron Nitride", ACS Appl. Mater. Interfaces* **8** (41), 27877–27884 (2016).

